

L Number	Hits	Search Text	DB	Time stamp
1	4621	mask with cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 13:23
2	900	(mask with cvd) with (precursor or vapor or (raw adj material))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 13:24
3	12	((mask with cvd) with (precursor or vapor or (raw adj material))) same silane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 13:25
4	68	427/248.1.ccls. and 427/282.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 15:31
5	48	hmids with vaporiz\$7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 15:41
6	11	("4459267" "4789564" "4870923" "4892615" "4924800" "5070814" "5203925" "5252134" "5278138" "5383970" "5501870").PN.	USPAT	2003/09/11 15:34
7	14	(427/901).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 15:46
8	936	427/256.ccls. and 427/(248.1-255.7).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 15:48
9	45	427/256.ccls. and 427/248.1-255.7.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 15:51
10	372	427/256-288.ccls. and (\$3cvd or (chemical adj vapor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 16:59
11	2	427/256-288.ccls. and (\$3cvd or (chemical adj vapor))	USOCR	2003/09/11 17:00
12	113	liquid with pattern with (vaporiz\$7 or evaporat\$6)	USOCR	2003/09/11 17:02
13	18	liquid with pattern with (vaporiz\$7 or evaporat\$6) with (substrate or wafer) with (portion or part)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/11 17:02